The 23<sup>rd</sup> Korean Conference on Semiconductors (KCS 2016)

## 제23회 한국반도체학술대회

2016년 2월 22일(월)-24일(수), 강원도 하이원리조트

## B. Patterning 분과

		Room I 육백 <b>피(6</b> 층)
2016년 2월 24일(수) 10:00-11:40 [WI2-B] Patterning 좌장 : 김현우(한양대학교)		
WI2-B-1	10:10-10:25	Effect of Etching Gas on Magnetic Tunnel Junction Stacks Etching using Inductively Coupled Plasma Reactive Ion Etching Su Min Hwang, Jae Yong Lee, Adrian Adalberto Garay, Ji Hyun Choi, and Chee Won Chung Department of Chemistry and Chemical Engineering, Center for Design and Applications of Molecular Catalysts, Inha University
WI2-B-2	10:25-10:40	Impact of Process Parameters on RLS in EUV Resist Simulation for 10-nm Pattern Formation Sang-Kon Kim <sup>1,2</sup> <sup>1</sup> Department of Applied Physics, Hanyang University, <sup>2</sup> Department of Science, Hongik University
WI2-B-3	10:40-10:55	OPC Optimization Techniques for Reducing The Mismatch Between Overlay Metrology and Device Pattern Cell Jae-hee Hwang, Shinyoung Kim, Chanha Park, Hyunjo Yang, and Donggyu Yim Research and Development Division, SK hynix Inc.
WI2-B-4	10:55-11:10	Investigation on Overlay Analysis using Design Based Metrology Tool Sangwoo Kim, Gyoyeon Jo, Sunkeun Ji, Shinyoung Kim, Hyunwoo Kang, Minwoo Park, Jungchan Kim, Chanha Park, Hyunjo Yang, and Donggyu Yim Research and Development Division, SK hynix Inc.
WI2-B-5	11:10-11:25	<b>Improving Same Colors Space Distribution in Multi Patterned</b> <b>Layers for Hotspots Reduction.</b> Dong-Gyun Kim <sup>1</sup> , Sung-Keun Park <sup>1</sup> , Young-Gook Park <sup>1</sup> , Jae-Seok Yang <sup>1</sup> , Jong-Hyun Lee <sup>1</sup> , Mostafa Shadoufa <sup>2</sup> , and Mohammed Harb <sup>2</sup> <sup>1</sup> Samsung Electronics Co., Ltd., <sup>2</sup> Mentor Graphics Corporation, Egypt
WI2-B-6	11:25-11:40	High Scan Speed ArF Immersion Scanner 에서 Topcoat-less Resist 가 가져야 할 특성에 관한 연구 손민석, 류윤정, 오창일, 반근도, 김겸, 박은주, 복철규, 김영식, 곽노정 <i>Research and Development Division, DRAM Process Group, SK hynix</i> <i>Inc.</i>